



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: **Wei-Yu Su**

Serial No.: **10/040,042**

Group Art Unit: **1746**

Filing Date: **November 7, 2001**

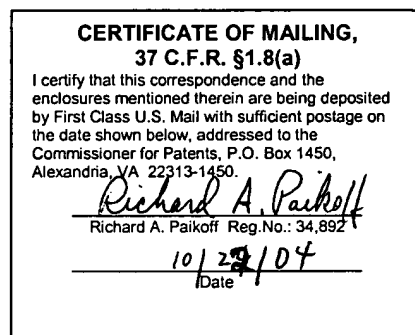
Examiner: **Zeinab El Arini**

For: **METHOD FOR REDUCTION OF PHOTOMASK DEFECTS**

**TRANSMITTAL LETTER**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:



Please find enclosed for filing:

- ☒ Amendment and Response under 37 CFR §116(a) to Official Action dated August 27, 2004
- ☒ Certificate of First Class Mail
- ☒ Please charge any additional fees to Deposit Account No. 04-1679
- ☒ Other: 1 Return Postcard

Respectfully submitted,

Dated: 10/22/04

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Docket No.: N1085-90003



AF/1746

IFW

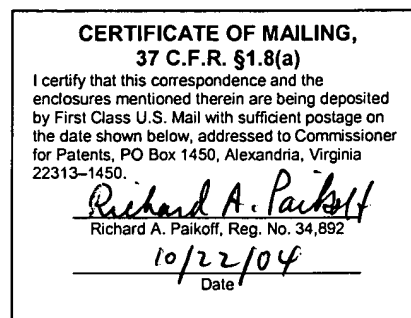
PATENT A

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : 10/040,042 Confirmation No. 1835  
Applicant : Wei-Yu Su  
Filed : November 7, 2001  
TC/A.U. : 1746  
Title : Method for Reduction of Photomask Defects

Docket No. : N1085-90003  
Customer No. : 08933

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450



AMENDMENT AND RESPONSE UNDER 37 CFR §116(a)

Sir:

In response to the Office Action of August 27, 2004, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 5 of this paper.